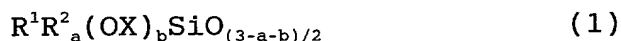


CLAIMS:

1. A surface treatment agent which, when applied to a substrate prior to formation of a resist pattern thereon, strengthens adhesion between the substrate and the resist pattern, the surface treatment agent comprising at least one compound of the following compositional formula:



- wherein R^1 is a $-(CH_2)_nY$ moiety in which Y is epoxycyclohexyl, glycidoxy, N- β -aminoethylamino, amino, N-phenylamino, mercapto or isocyanate, and n is an integer from 0 to 4; R^2 is a monovalent hydrocarbon group of 1 to 4 carbons; X is hydrogen or a monovalent hydrocarbon group of 1 to 4 carbons; "a" is 0 or 1, and "b" is 0, 1 or 2 when "a" is 0, and "b" is 0 or 1 when "a" is 1.

2. The surface treatment agent of claim 1, wherein the compound of compositional formula (1) is prepared by hydrolyzing a silane of general formula (2):



- wherein R^1 , R^2 and "a" are as defined above; Z is a monovalent hydrocarbon group of 1 to 4 carbons; and "c" is a number which satisfies the condition $a+c = 3$.

3. The surface treatment agent of claim 1, wherein R^1 is selected from the group consisting of β -(3,4-epoxycyclohexyl)ethyl, γ -aminopropyl, γ -mercaptopropyl, γ -isocyanatepropyl, N- β -(aminoethyl)- γ -aminopropyl, γ -glycidoxypropyl and N-phenyl- γ -aminopropyl.

4. A patterning process comprising the steps of applying the surface treatment agent of claim 1 to a substrate and baking, then applying thereon a photoresist composition and patterning the photoresist.

5. The patterning process of claim 4, wherein the substrate is a metal or metal oxide substrate.

6. The patterning process of claim 5, wherein the metal
5 or metal oxide making up the substrate is aluminum, iron,
nickel, copper, tantalum, gold, or an oxide thereof.